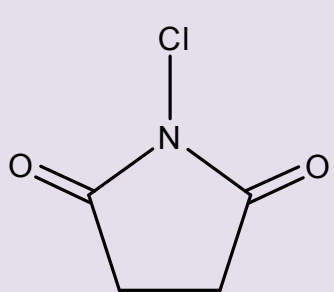
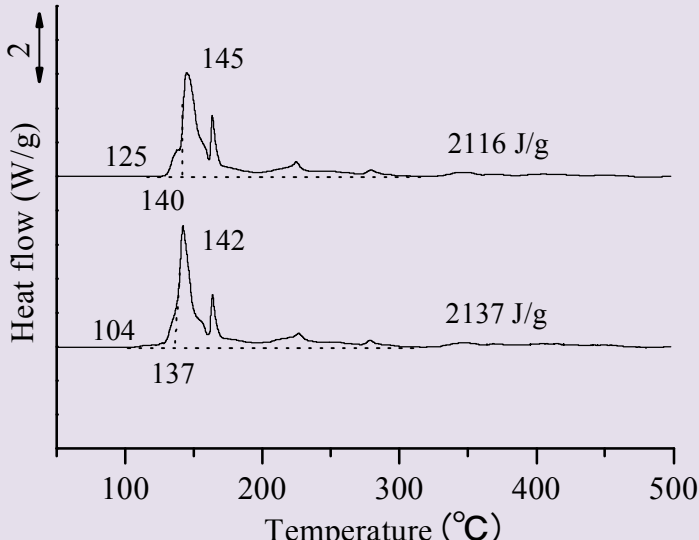
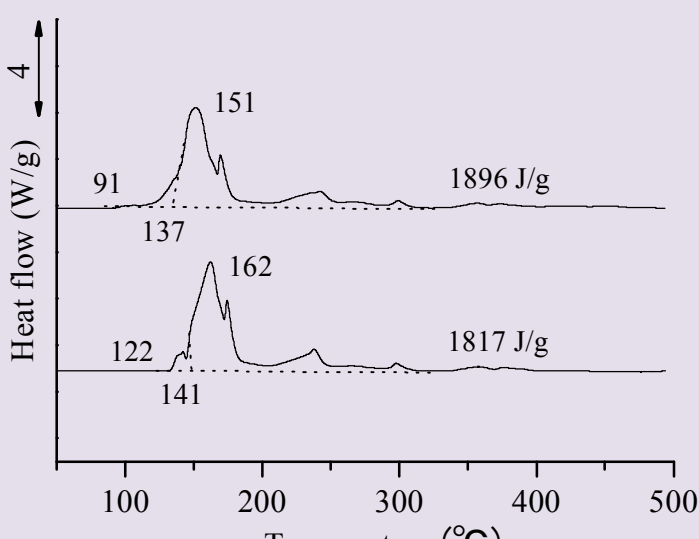
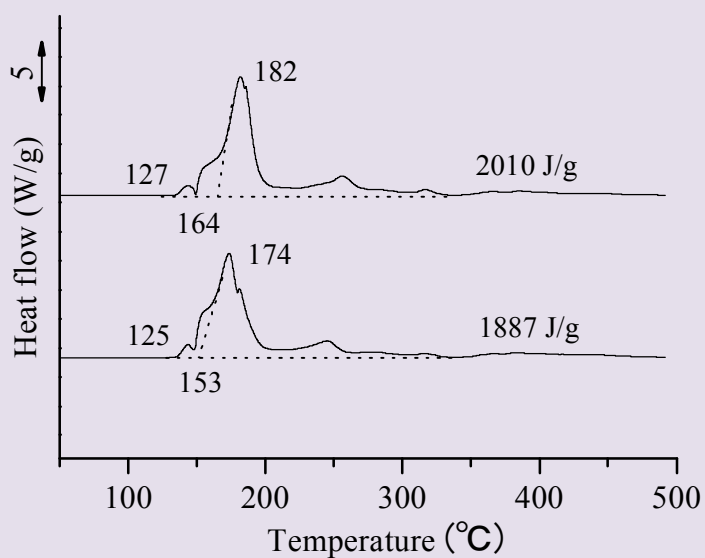


<p>N-Chlorosuccinimide</p>	<p><math>C_4H_4ClNO_2</math> NCSI</p>
	<p>DSC device: SII DSC 7020                  SII Nano Technology Inc.                  dT/dt: 2, 5, 10, 20 K/min                  Atmosphere: Air                  Vesel: pressure vessel (SUS)                  SII Nano Technology Inc.                  Sample: Wako ( <math>\geq 97.0\%</math> )</p>
<p>a) 2 K/min <span style="float: right;">Wako: 和光純薬工業株式会社</span></p>	
	<p>&lt; Average &gt;  <math>T_a</math>: 115 °C  <math>T_o</math>: 139 °C  <math>T_{top}</math>: 144 °C  <math>Q_{DSC}</math>: 2127 J/g</p>
<p>b) 5 K/min</p>	
	<p>&lt; Average &gt;  <math>T_a</math>: 107 °C  <math>T_o</math>: 139 °C  <math>T_{top}</math>: 157 °C  <math>Q_{DSC}</math>: 1857 J/g</p>

c) 10 K/min



< Average >

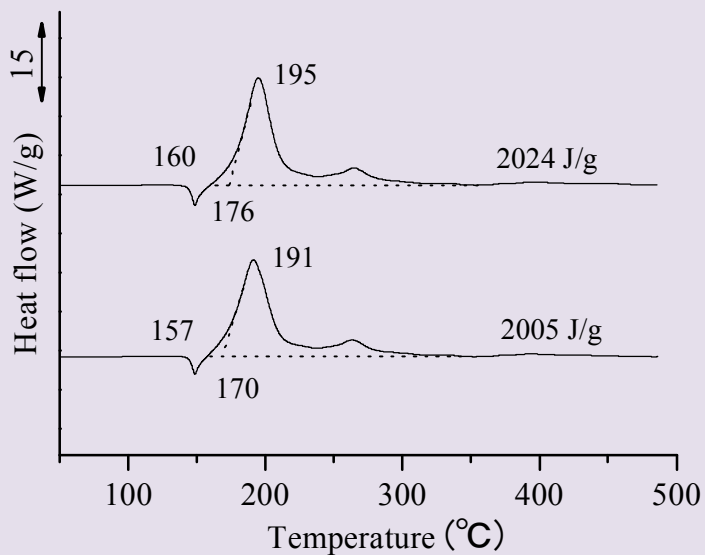
$T_a$  : 126 °C

$T_o$  : 159 °C

$T_{top}$  : 178 °C

$Q_{DSC}$  : 1949 J/g

d) 20 K/min



< Average >

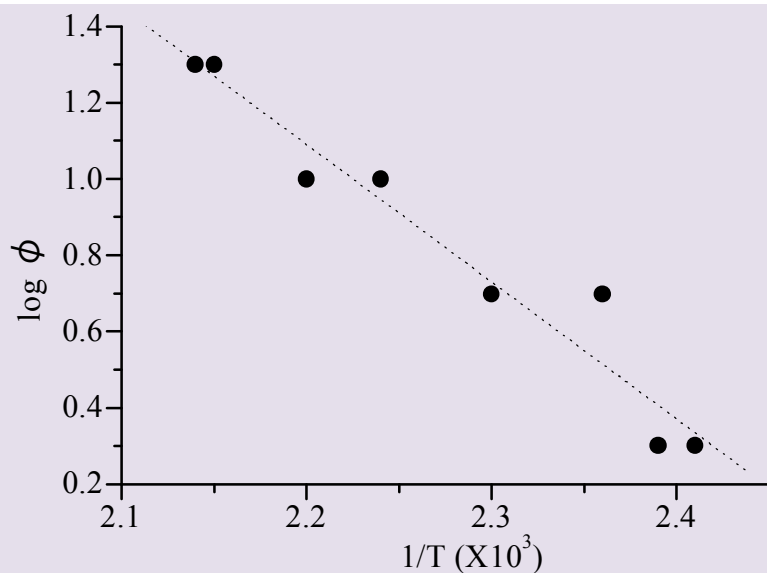
$T_a$  : 159 °C

$T_o$  : 173 °C

$T_{top}$  : 193 °C

$Q_{DSC}$  : 2015 J/g

## ASTM PLOT



$\Delta E : 67 \text{ kJ/mol}$   
 $A : 4.50 \times 10^{11}$   
 $r : -0.97253$

Heat rate $\phi$ (K/min)	$T_{\text{peak}}$ (°C)	$T_m$ (K)	$1/T_m \cdot 10^3$	$\log \phi$
2	145	418	2.39	0.301
	142	415	2.41	0.301
5	151	424	2.36	0.699
	162	435	2.30	0.699
10	182	455	2.20	1.00
	174	447	2.24	1.00
20	195	468	2.14	1.30
	191	464	2.15	1.30